

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Appln. of: Jürgen HOLZ ET AL.

Appln. No.: Not yet assigned

Filed: Herewith

For: FIELD-EFFECT TRANSISTOR  
WITH LOCAL SOURCE/DRAIN  
INSULATION AND  
ASSOCIATED FABRICATION  
METHOD

Examiner: Not yet assigned

Art Unit: N/A

Attorney Docket No: 10808/231

## INFORMATION DISCLOSURE STATEMENT

In accordance with the duty of disclosure under 37 C.F.R. §1.56 and §§1.97-1.98, and more particularly in accordance with 37 C.F.R. §1.97(b), Applicants hereby cite the following reference(s):

No.	Date of Publication	Patentee/Applicant/Assignee
US 2002/0142552 A1	October 3, 2002	Wu
6,403,482	June 11, 2002	Rovedo et al.
6,346,729 B1	February 12, 2002	Liang et al.
US 2001/0025998 A1	October 4, 2001	Tsuchiaki
US 2001/0017387 A1	August 30, 2001	Hsich et al.
5,949,116	September 7, 1999	Wen
5,908,313	June 1, 1999	Chau et al.
5,620,912	April 15, 1997	Hwang et al.
5,043,778	August 27, 1991	Teng et al.
<b>FOREIGN PATENT DOCUMENTS</b>		
DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	COUNTRY
WO 02/43109 A2	March 30, 2002	WO
WO 01/50535 A2	July 12, 2001	WO
DE 198 12 643 C1	July 8, 1999	Germany
DE 197 49 378 A1	May 20, 1999	Germany
<b>OTHER ART – NON PATENT LITERATURE DOCUMENTS</b>		
Norbert Elbel, Zvonimir Gabric, Wolfram Langheinrich and Bernard Neureither, <i>A New STI Process Based on Selective Oxide Deposition</i> , pgs. 208-209, Symposium on VLSI Technology Digest of Technical Papers, IEEE, 1998.		
N.G. Anantha, C.T. Horng, R.R. Konian and R.E. Matick, <i>Self-Aligned Igfet With Silicon Dioxide Isolated Source and Drain</i> , pgs. 4895-4899, IBM Technical Disclosure Bulletin, Vol 22, No. 11, April 1980.		
Copy of International Search Report from corresponding PCT patent application no. PCT/DE03/03130.		
Copy of Examination Report from corresponding PCT patent application no. PCT/DE03/03130.		


Applicants are enclosing Form PTO-1449 (one sheet), along with a copy of each listed reference for which a copy is required under 37 C.F.R. §1.98(a)(2). As each of the listed references is in English, no further commentary is believed to be necessary, 37 C.F.R §1.98(a)(3). Applicants respectfully request the Examiner's consideration of the above reference(s) and entry thereof into the record of this application.

By submitting this Statement, Applicants are attempting to fully comply with the duty of candor and good faith mandated by 37 C.F.R. §1.56. As such, this Statement is not intended to constitute an admission that any of the enclosed references, or other information referred to therein, constitutes "prior art" or is otherwise "material to patentability," as that phrase is defined in 37 C.F.R. §1.56(a).

Applicants have calculated no fee to be due in connection with the filing of this Statement. However, the Director is authorized to charge any fee deficiency associated with the filing of this Statement to a deposit account, as authorized in the Transmittal accompanying this Statement.

4/7/05  
 \_\_\_\_\_  
 Date

Respectfully submitted,

  
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 Anthony P. Curtis, Ph.D.  
 (Reg. No. 46,193)

FORM PTO-1449	SERIAL NO. Not yet assigned	CASE NO. 10808/231
<b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b>	FILING DATE	GROUP ART UNIT
	Herewith	N/A
(use several sheets if necessary)		APPLICANT(S): Jürgen HOLZ ET AL.

**REFERENCE DESIGNATION                      U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
	A1	US 2002/0142552 A1	October 3, 2002	Wu	
	A2	6,403,482	June 11, 2002	Rovedo et al.	
	A3	6,346,729 B1	February 12, 2002	Liang et al.	
	A4	US 2001/0025998 A1	October 4, 2001	Tsuchiaki	
	A5	US 2001/0017387 A1	August 30, 2001	Hsich et al.	
	A6	5,949,116	September 7, 1999	Wen	
	A7	5,908,313	June 1, 1999	Chau et al.	
	A8	5,620,912	April 15, 1997	Hwang et al.	
	A9	5,043,778	August 27, 1991	Teng et al.	

**FOREIGN PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
	A10	WO 02/43109 A2	March 30, 2002	WO	
	A11	WO 01/50535 A2	July 12, 2001	WO	
	A12	DE 198 12 643 C1	July 8, 1999	Germany	
	A13	DE 197 49 378 A1	May 20, 1999	Germany	

EXAMINER INITIAL	OTHER ART – NON PATENT LITERATURE DOCUMENTS <small>(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.</small>
	A14 Norbert Elbel, Zvonimir Gabric, Wolfram Langheinrich and Bernard Neureither, <i>A New STI Process Based on Selective Oxide Deposition</i> , pgs. 208-209, Symposium on VLSI Technology Digest of Technical Papers, IEEE, 1998.
	A15 N.G. Anantha, C.T. Horng, R.R. Konian and R.E. Matlick, <i>Self-Aligned Igfet With Silicon Dioxide Isolated Source and Drain</i> , pgs. 4895-4899, IBM Technical Disclosure Bulletin, Vol 22, No. 11, April 1980.
	A16 Copy of International Search Report from corresponding PCT patent application no. PCT/DE03/03130.
	A17 Copy of Examination Report from corresponding PCT patent application no. PCT/DE03/03130.

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.